	Sheet 1 of 1
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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO. 26860/33:47 US

SERIAL NO. 08/651,036

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APPLICANT

Mark D. Owen, Bonnie A. Larson, Jozef Van Puymbroeck

FILING DATE May 17, 1996 GROUP 2106

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Gm	AC	5	1	9	4	7	1	3	03/16/93	Egitto et al.	219	121.71	
am	AD	5	1	6	8	4	5	4	12/01/92	LaPlante et al.	219	121.8	
G M	AE	5	1	5	3	4	0	8	10/06/92	Handford et al.	219	121.64	
hm	AF	5	1	0	8	7	8	5	04/28/92	Lincoln et al.	427	96	- 10
Lm	AG	5	0	8	7	3	9	6	02/11/92	Zablotny et al.	-264	25	
am	AH	5	0	7	3	6	8	7	12/17/91	Inagawa et al.	219	121.7	AUG 2 2 1996
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c m	AJ	4	9	1	5	9	8	1	04/10/90	Traskos et al.	427	53.1	
am	AK	4	8	9	4	1	1	5	01/16/90	Eichelberger et al.	219	121.69	
4 m	AL	4	8	3	2	7	8	8	05/23/89	Nemiroff	156	643	
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FOREIGN PATENT DOCUMENTS

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INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)

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